

What is claimed is:

1. A positive type resist composition comprising:

(A) a resin having a monocyclic or polycyclic alicyclic hydrocarbon structure, which increases the solubility in an alkali developing solution by the action of an acid;

(B) a compound capable of generating an acid upon irradiation with an actinic ray or a radiation; and

(C) an alkoxy alcohol as a solvent, wherein an alkoxy group and an alcoholic hydroxyl group are connected to each other via at least three carbons.

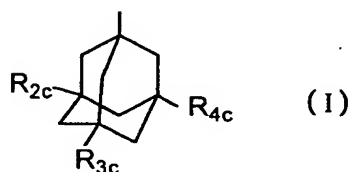
2. The composition according to claim 1, wherein the solvent (C) further contains a propylene glycol monoalkyl ether carboxylate.

3. The composition according to claim 2, wherein the solvent (C) contains from 10 to 50 % by weight of the alkoxy alcohol and from 50 to 90 % by weight of the propylene glycol monoalkyl ether carboxylate.

4. The composition according to claims 1, wherein the alkoxy alcohol is 3-methoxybutanol.

5. The composition according to claim 2, wherein the propylene glycol monoalkyl ether carboxylate is propylene glycol monomethyl ether acetate.

6. The composition according to claim 1, wherein the resin (A) comprises a repeating unit having a group represented by the following formula (I):



wherein R_{2c}, R_{3c}, and R_{4c} each independently represents a hydrogen atom or a hydroxyl group, provided that at least one of R_{2c}, R_{3c}, and R_{4c} represents a hydroxyl group.

7. The composition according to claim 1, wherein the resin (A) comprises a repeating unit having an alkali-soluble group protected by a 2-alkyl-2-adamantyl group or a 1-adamantyl-1-alkylalkyl group.

8. The composition according to claim 1, wherein the compound (B) is a compound capable of generating a perfluorobutanesulfonic acid or a perfluorooctanesulfonic acid upon irradiation with an actinic ray or a radiation.

9. The composition according to claim 1, wherein the alkoxy group and the alcoholic hydroxyl group are connected to each other via from 3 to 10 carbons.

10. The composition according to claim 1, wherein the alkoxy alcohol has a boiling point of from 120 to 220 °C.

11. The composition according to claim 1, further comprising (D) a nitrogen-containing basic compound:

12. The composition according to claim 1, further comprising (E) a fluorine based and/or silicon based surfactant:

13. A method for forming a pattern, which comprises forming a resist film comprising the composition described in claim 1, exposing the resist film upon irradiation with the actinic rays or a radiation, and subsequently developing the resist film.